

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) A lithographic projection apparatus, comprising:
a radiation system constructed to provide a beam of radiation;
a support structure to support a patterning device, said patterning device serving to pattern said beam of radiation according to a desired pattern and form a patterned beam;
a substrate table for supporting a substrate;
a projection system that projects said patterned beam onto a target portion of said substrate; and
at least one holding structure having at least one compliant member constructed to hold a pimple plate, said pimple plate constructed to hold one of said patterning device and said substrate.
2. (Original) A lithographic projection apparatus according to claim 1, wherein said at least one compliant member includes a membrane.
3. (Original) A lithographic projection apparatus according to claim 1, wherein said at least one compliant member includes a pair of parallel flaps.
4. (Original) A lithographic projection apparatus according to claim 3, wherein each of said pair of parallel flaps is supported along the respective length of each of said pair of parallel flaps.
5. (Original) A lithographic projection apparatus according to claim 1, wherein said pimple plate is substantially rigid in comparison with said at least one compliant member.
6. (Original) A lithographic projection apparatus according to claim 1, further comprising:
a plurality of supports for supporting said at least one of said patterning device and said substrate and each of said plurality of supports extending substantially perpendicular to a

plane of said at least one of said patterning device and said substrate.

7. (Original) A lithographic projection apparatus according to claim 6, wherein said plurality of supports are arranged to support said pimple plate at Bessel points.

8. (Original) A lithographic projection apparatus according to claim 7, wherein said plurality of supports is three fixed supports.

9. (Original) A lithographic projection apparatus according to claim 6, wherein at least one of said plurality of supports provides electrical contact with said pimple plate.

10. (Original) A lithographic projection apparatus according to claim 1, further comprising:

an electrostatic clamp constructed to clamp said pimple plate to at least one of said one of said patterning device and said substrate and said at least one compliant member.

11. (Original) A lithographic projection apparatus according to claim 1, wherein said beam of radiation comprises EUV radiation.

12. (Original) A lithographic projection apparatus according to claim 1, wherein said at least one of said support structure and said substrate table includes said at least one holding structure.

13. (Currently Amended) A method of manufacturing a device using a lithographic projection apparatus comprising:

providing a beam of radiation;

providing a support structure for supporting a patterning device;

using the patterning device to pattern the beam of radiation according to a desired pattern forming a patterned beam;

providing a substrate table for supporting a substrate;

holding one of the ~~patterned beam patterning device~~ and the substrate on a pimple plate during operation of the apparatus;

holding the pimple plate on at least one compliant member; and

projecting the patterned beam onto a target portion of the substrate.

14. (Currently Amended) A lithographic projection apparatus, comprising:
means for projecting ~~said~~ a patterned beam of radiation onto a target portion of a substrate;
holding means for holding at least one of a patterning device and said substrate; and
means for resiliently supporting said holding means.
15. (Original) A lithographic projection apparatus, comprising:
a radiation system constructed to provide a beam of radiation;
a pimple plate having protrusions extending from a surface, said pimple plate
constructed to hold a removable item on said protrusions;
a holding structure having at least one compliant member constructed to resiliently
hold said pimple plate.
16. (Original) A lithographic projection apparatus according to claim 15, wherein:
said removable item is one of a patterning device serving to pattern said beam of
radiation according to a desired pattern and form a patterned beam and a substrate.